

10/791,263

H1582

Amendment to the Specification

Please replace paragraph [0014] of the specification with the following:

[0014] According to still another aspect of the invention, a method of lithography include re-configuring, between lithography operations, reflective facets of a multi-faceted mirror that is part of a reflective condenser, wherein the re-configuring results in altering of light characteristics of light exiting the reflective condenser to strike a reflective reticle.

[0014.1] According to a further aspect of the invention, a lithography system includes: a light source; a reflective reticle; and a re-configurable reflective condenser that directs light from the light source to the reflective reticle. The reflective condenser includes a re-configurable multi-faceted mirror.